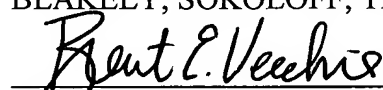


## REMARKS

The Applicants would like to notify the Examiner of an Intel patent pertaining to two-mask exposure lithography. The patent is U.S. Patent No. 6,632,576, entitled "OPTICAL ASSIST FEATURE FOR TWO-MASK EXPOSURE LITHOGRAPHY", filed December 30, 2000, by Edita Tejnil.

Respectfully submitted,  
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